

Notice of References Cited

Application/Control No.

10/020,407

Applicant(s)/Patent Under

Reexamination

MADGE ET AL.

Examiner

Judith A. Cothorn

Art Unit

2822

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	V	Sabade et al. "Improved wafer-level spatial analysis for IDQ limit setting", Test Conference, 2001, Proceedings. International, pp. 82-91.
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	X	Thibeault, C., "Improving delta-IDQ-based test methods", International Test Conference, 2000, pp.207-216.

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.